

PTO-1449

**Information Disclosure Citation
in an Application**

Application No.

10/696,326

Applicant(s)

Zhang et al.

Docket Number

064441.0266

Group Art Unit

1756

Filing Date

10/29/2003

U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>AB</i>	3927943	12/23/75	Pohl et al.	355	132	07/01/74
B.	4032233	06/28/77	Oscarsson et al.	355	91	05/03/76
C.	4131363	12/26/78	Shea et al.	355	75	12/05/77
D.	4159176	06/26/79	de Masi	355	79	11/14/77
E.	4255216	03/10/81	Conant et al.	156	80	01/14/80
F.	4470508	09/11/84	Yen	206	334	08/19/83
G.	4536240	08/20/85	Winn	156	74	02/22/83
H.	4584216	04/22/86	Kenworthy et al.	428	38	06/15/84
I.	4657805	04/14/87	Fukumitsu et al.	428	215	06/13/85
J.	4737387	04/12/88	Yen	428	14	07/07/86
K.	4833051	05/23/89	Imamura	430	5	12/17/87
L.	4948851	08/14/90	Squire	526	247	12/28/89
M.	4973142	11/27/90	Squire	350	409	04/09/90
N.	5008156	04/16/91	Hong	428	506	12/06/98
<i>RC</i>	5061024	10/29/91	Keys	359	350	09/06/89

FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<i>AP</i>	2000292909	10/20/00	JP (abstract only)	G03F	1/14	X	
<i>AQ</i>	10062966	03/06/98	JP (abstract only)	G03F	1/14	X	

NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
<i>AR</i>	International PCT Search Report with Notification of Transmittal, PCT/US03/34485, 8 pages.	Mailed 07/29/04
<i>AS</i>	Bernal, M.P. et al., "Natural Zeolites and Sepiolite as Ammonium and Ammonia Adsorbent Materials", Bioresource Technology 43 (1993) pp. 27-33.	1993
<i>AT</i>	Bernal, M.P. et al., "Application of Natural Zeolites for the Reduction of Ammonia Emissions during the Composting of Organic Wastes in a Laboratory Composting Simulator", Bioresource Technology 43 (1993) pp. 35-39.	1993
<i>AU</i>	Grayfer et al., "Protecting 248 nm Lithography from Airborne Molecular Contamination during Semiconductor Fabrication", Proceedings of SPIE Vol. 4346 (2001), pp. 676-694. Optical Microlithography XIV.	2001

EXAMINER

A. Rosasco

DATE CONSIDERED

5-31-05

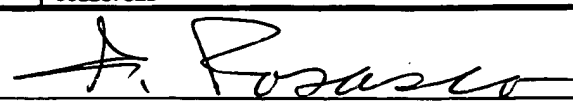
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U.S. PATENT DOCUMENTS							
	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
<input checked="" type="checkbox"/>	A.	5260585	11/09/93	Tom	250	573	06/12/92
<input checked="" type="checkbox"/>	B.	5487771	01/30/96	Zeller	55	523	07/27/94
<input checked="" type="checkbox"/>	C.	5723860	03/03/98	Hamada et al.	250	239	06/28/96
<input checked="" type="checkbox"/>	D.	5856018	01/05/99	Chen et al.	428	448	06/17/96
<input checked="" type="checkbox"/>	E.	5928410	07/27/99	Jois et al.	95	51	12/09/97
<input checked="" type="checkbox"/>	F.	6083577	07/04/00	Nakagawa et al.	428	14	03/17/98
<input checked="" type="checkbox"/>	G.	6149992	11/21/00	Nakayama	428	14	10/19/98
<input checked="" type="checkbox"/>	H.	6254942	07/03/01	Tanaka	428	14	06/07/00
<input checked="" type="checkbox"/>	I.	6277342	08/21/01	Pearlstein et al.	423	210	08/23/99
<input checked="" type="checkbox"/>	J.	6383258	05/07/02	Simmons	95	45	12/19/00
<input checked="" type="checkbox"/>	K.	6395066	05/28/02	Tanihara et al.	95	47	02/23/00
<input checked="" type="checkbox"/>	L.	6428583	08/06/02	Reuter	23	301	04/27/00

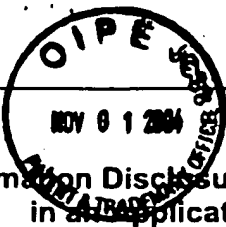
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<input checked="" type="checkbox"/>	M.	2001350252	12/21/01	JP (abstract only)	G03F	1/14	X
<input checked="" type="checkbox"/>	N.	04196117	07/15/92	JP (abstract only)	H01L	21/027	X
<input checked="" type="checkbox"/>	O.	10198021	07/31/98	JP (abstract only)	G03F	1/14	X
<input checked="" type="checkbox"/>	P.	01/59522 A1	08/16/01	WO	G03F	1/14	X
<input checked="" type="checkbox"/>	Q.	2004/031855 A2	04/15/04	WO	G03F	-	X
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<input type="checkbox"/>	S.						

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	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
<input checked="" type="checkbox"/>	T. Kinkead et al., "Targeting Gaseous Contaminants in Wafer FABS: Fugitive Amines", Microcontamination, pp. 37-40.	06/1993
<input checked="" type="checkbox"/>	U. Cullins et al., "157-nm Photomask Handling and Infrastructure: Requirements and Feasibility", Proceedings of SPIE Vol. 4409 (2001), pp. 632-640, Photomask and Next-Generation Lithography Mask Technology VIII; XP-002287329	2001

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	A.	6433356	08/13/02	Cahen et al.	257	40	07/14/99	
	B.	6435586	08/20/02	Getzschman et al.	296	37.6	04/13/01	
	C.	6436586	08/20/02	Matsuoka et al.	430	5	04/06/00	
	D.	6443302	09/03/02	Tanaka	206	316.1	04/26/01	
	E.	6444608	09/03/02	Oki et al.	502	300	10/17/01	
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	P.						
	Q.						
NON-PATENT DOCUMENTS							
		DOCUMENT (Including Author, Title, Source, and Pertinent Pages)					DATE
	R.	Kishkovich, Oleg, et al., "Airborne Molecular Contamination Control for DUV Lithography", Cleanroom Technology, vol. 6(5), pp. 31-33.					June 2000
	S.						
	T.						
	U.						
EXAMINER <i>A. Trasco</i>					DATE CONSIDERED 5-31-05		
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